

Title (en)
SOURCE REAGENT COMPOSITIONS AND METHOD FOR FORMING METAL FILMS ON A SUBSTRATE BY CHEMICAL VAPOR DEPOSITION

Title (de)
REAGENZZUSAMMENSETZUNG UND VERFAHREN ZUR BILDUNG VON METALLSCHICHTEN AUF SUBSTRATEN MITTELS CHEMISCHER GASPHASENABSCHEIDUNG

Title (fr)
COMPOSITIONS DE REACTIF DE SOURCE ET PROCEDE POUR FORMER DES FILMS METALLIQUES SUR UN SUBSTRAT PAR DEPOT CHIMIQUE EN PHASE VAPEUR

Publication
EP 1313744 A4 20040331 (EN)

Application
EP 01964374 A 20010823

Priority
• US 0126339 W 20010823
• US 64954900 A 20000828

Abstract (en)
[origin: WO0218394A1] A metalorganic complex composition comprising a metalorganic complex selected from the group consisting of: metalorganic complexes comprising one or more metal central atoms coordinated to one or more monodentate or multidentate organic ligands, and complexed with one or more complexing monodentate or multidentate ligands containing one or more atoms independently selected from the group consisting of atoms of the elements C, N, H, So, O and F; wherein when the number of metal atoms is one and concurrently the number of complexing monodentate or multidentate ligands is one, then the complexing monodentate or multidentate ligand of the metalorganic complex is selected from the group consisting of beta-ketoiminates, beta-diiminates, C2-C10 alkenyl, C2-C15 cycloalkenyl and C6-C10 aryl.

IPC 1-7
C07F 9/00

IPC 8 full level
C07C 49/92 (2006.01); **C07F 1/00** (2006.01); **C07F 3/00** (2006.01); **C07F 5/00** (2006.01); **C07F 5/06** (2006.01); **C07F 7/00** (2006.01); **C07F 7/28** (2006.01); **C07F 9/00** (2006.01); **C07F 9/94** (2006.01); **C07F 11/00** (2006.01); **C07F 15/00** (2006.01); **C23C 16/18** (2006.01); **C23C 16/30** (2006.01); **C23C 16/40** (2006.01)

CPC (source: EP)
C07F 1/005 (2013.01); **C07F 3/003** (2013.01); **C07F 5/003** (2013.01); **C07F 5/069** (2013.01); **C07F 7/003** (2013.01); **C07F 9/005** (2013.01); **C07F 9/94** (2013.01); **C07F 11/005** (2013.01); **C07F 15/004** (2013.01); **C23C 16/18** (2013.01); **C23C 16/305** (2013.01); **C23C 16/40** (2013.01)

Citation (search report)
• [DY] US 5280012 A 19940118 - KIRLIN PETER S [US], et al
• [DY] US 5204314 A 19930420 - KIRLIN PETER S [US], et al
• [DY] US 5225561 A 19930706 - KIRLIN PETER S [US], et al
• [Y] US 4501602 A 19850226 - MILLER STEPHEN B [US], et al
• [Y] WO 9927030 A1 19990603 - ADVANCED TECH MATERIALS [US]
• [Y] WO 9900530 A1 19990107 - ADVANCED TECH MATERIALS [US], et al
• [Y] WO 9608587 A1 19960321 - ADVANCED TECH MATERIALS [US]
• [Y] US 5820664 A 19981013 - GARDINER ROBIN A [US], et al
• [Y] WO 9640690 A1 19961219 - ADVANCED TECH MATERIALS [US]
• [Y] JONES, ANTHONY C. ET AL: "Metal-organic chemical vapour deposition of lead scandium tantalate: chemical issues and precursor selection", POLYHEDRON (2000), 19(3), 351-355, XP002268230
• See references of WO 0218394A1

Designated contracting state (EPC)
AT BE CH DE FR IT LI

DOCDB simple family (publication)
WO 0218394 A1 20020307; AU 8523501 A 20020313; EP 1313744 A1 20030528; EP 1313744 A4 20040331; JP 2004507551 A 20040311

DOCDB simple family (application)
US 0126339 W 20010823; AU 8523501 A 20010823; EP 01964374 A 20010823; JP 2002523909 A 20010823